

REMARKS

Claims 1-25 are all the claims pending in the application.

I. Formal Matters - Claim 19

In the Amendment dated August 23, 2002, it appears that Applicants' representative inadvertently left structural formula (pVI) out of the amendment to claim 19. Claim 19 is amended herein to insert the missing structural formula (pVI).

II. The Allowable Subject Matter

The Examiner has not included claims 4, 12 and 21 in the rejection. Further, on the Office Action cover page, the Examiner indicates that claims 4, 12 and 21 are "objected to."

The Examiner is requested to clarify that claims 4, 12 and 21 are allowable, but objected to as being dependent from rejected base claims.

III. The Rejection Based on Nozaki et al

Claims 1-3, 5-11, 13-20 and 22-25 are rejected under 35 U.S.C. §102(e) as allegedly being anticipated by Nozaki et al.

The Examiner considers Nozaki et al to disclose photoresist compositions containing resins that are within the scope of Applicants' claimed resins. The Examiner particularly notes Examples 3, 4, 8, 13-16 and 66-68, which the Examiner alleges disclose a copolymer comprising mevalonic lactone and an alicyclic containing methacrylate or an adamantyl methacrylate derivative.

Applicants respectfully submit that the present invention is not anticipated by the disclosures of Nozaki et al and request that the Examiner reconsider and withdraw this rejection in view of the following remarks.

Applicants respectfully submit that the resins of Nozaki et al are not within the scope of the resins of the present invention. The resins of the present invention are characterized in the position of the substituent on the lactone of the formula (I).

Formula (I) of the present invention recites that a substituent is introduced into each of R₆ and R₇ of the formula (I) in the present invention. The mevalonic lactone structure in Nozaki et al is represented in formula (XLIII) of column 31, in which a methyl group is introduced into the position corresponding to R₁ in the formula (I) of the present invention. Another structure in Nozaki et al is represented in Example 66 of column 71, in which a methyl group is introduced into each of the positions corresponding to R₄ and R₅ in formula (I) of the present invention. Each of said two compounds of Nozaki et al do not have a substituent in the position corresponding to R₆ and R₇ of the formula (I) in the present invention. Accordingly, Applicants respectfully submit that Nozaki et al does not teach or disclose Applicants' claimed invention.

For the above reasons, it is respectfully submitted that the subject matter of claims 1-3, 5-11, 13-20 and 22-25 is neither taught by nor made obvious from the

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disclosures of Nozaki et al and it is requested that the rejection under 35 U.S.C. §102 be reconsidered and withdrawn.

IV. Conclusion

In view of the above, Applicants respectfully submit that their claimed invention is allowable and ask that the rejection under 35 U.S.C. §102 be reconsidered and withdrawn. Applicants respectfully submit that this case is in condition for allowance and allowance is respectfully solicited.

If any points remain at issue which the Examiner feels may be best resolved through a personal or telephone interview, the Examiner is kindly requested to contact the undersigned at the local exchange number listed below.

Applicants hereby petition for any extension of time which may be required to maintain the pendency of this case. The USPTO is directed and authorized to charge all required fees, except for the Issue Fee and the Publication Fee, to Deposit Account No. 19-4880. Please also credit any overpayments to said Deposit Account.

Respectfully submitted,

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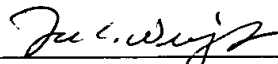
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PATENT TRADEMARK OFFICE

Date: March 5, 2003



Lee C. Wright
Registration No. 41,441



APPENDIX

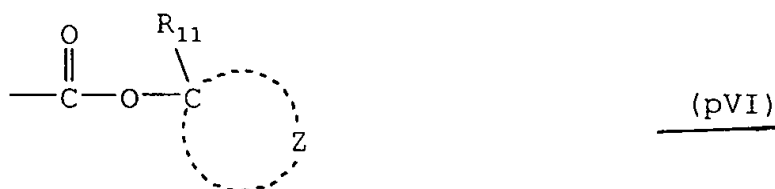
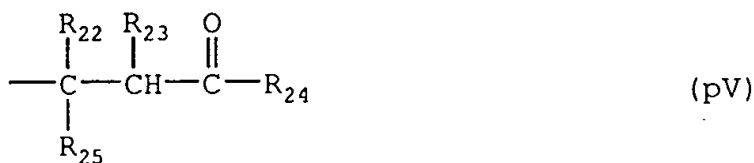
VERSION WITH MARKINGS TO SHOW CHANGES MADE

IN THE CLAIMS:

The claim 19 is amended as follows:

19 (twice Amended). The positive photoresist composition for far ultraviolet exposure as claimed in claim 18, wherein the resin (B) further contains a repeating unit having an alkali-soluble group protected by at least one group containing an alicyclic hydrocarbon structure represented by the following formula (pI), (pII), (pIII), (pIV), (pV) or (pVI):





wherein R₁₁ represents a methyl group, an ethyl group, an n-propyl group, an isopropyl group, an n-butyl group, an isobutyl group or a sec-butyl group; Z represents an atomic group necessary for forming an alicyclic hydrocarbon group together with the carbon atom; R₁₂ to R₁₆ each independently represents a linear or branched alkyl group having from 1 to 4 carbon atoms or an alicyclic hydrocarbon group, provided that at least one of R₁₂ to R₁₄ or either one of R₁₅ and R₁₆ represents an alicyclic hydrocarbon group; R₁₇ to R₂₁ each independently represents hydrogen atom, a linear or branched alkyl group having from 1 to 4 carbon atoms or an alicyclic hydrocarbon group, provided that at least one of R₁₇ to R₂₁ represents an alicyclic hydrocarbon group and either one of R₁₉ and R₂₁ represents a linear or

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branched alkyl group having from 1 to 4 carbon atoms or an alicyclic hydrocarbon group; and R_{22} to R_{25} each independently represents a linear or branched alkyl group having from 1 to 4 carbon atoms or an alicyclic hydrocarbon group, provided that at least one of R_{22} to R_{25} represents an alicyclic hydrocarbon group.